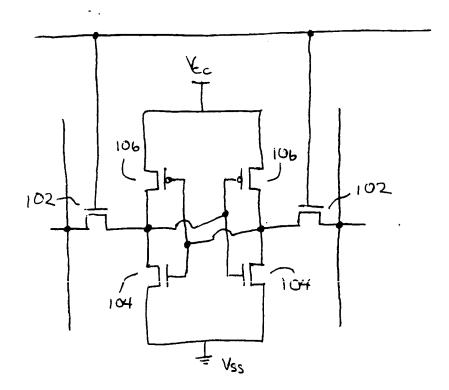
Fig. 1 - Prior Art



## Fig 2 - PRIOR ART

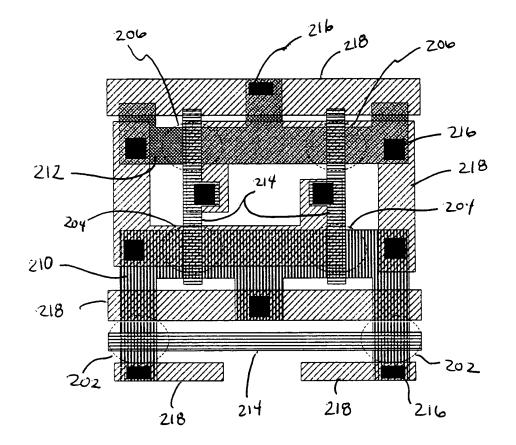
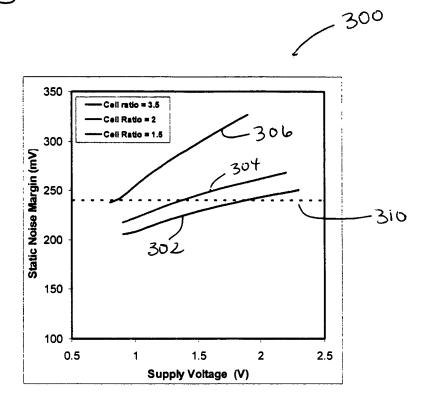
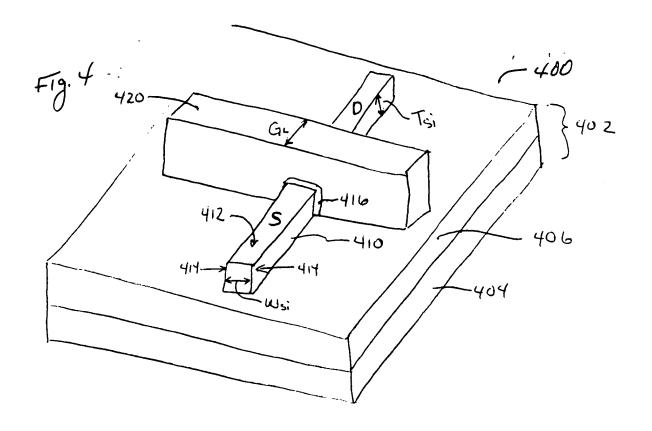


Fig.3





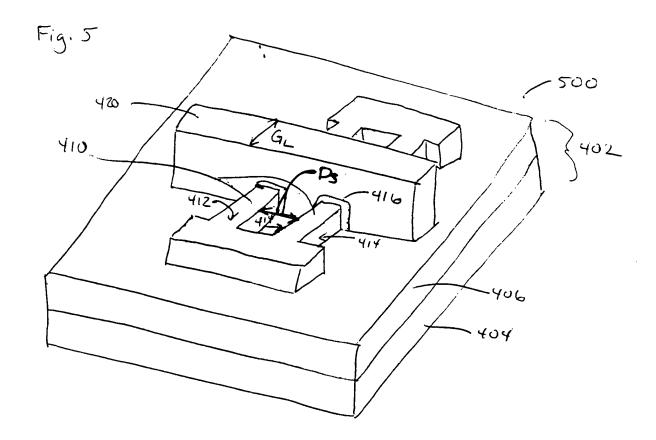


Fig. 6

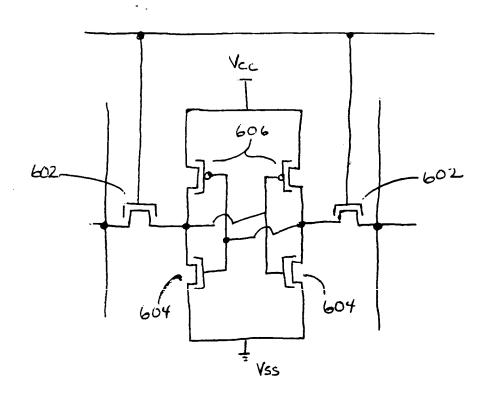


Fig. 7

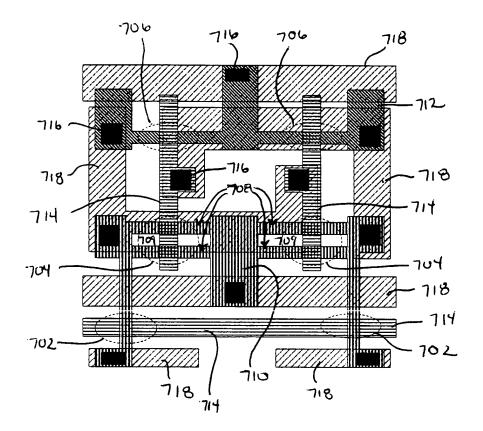
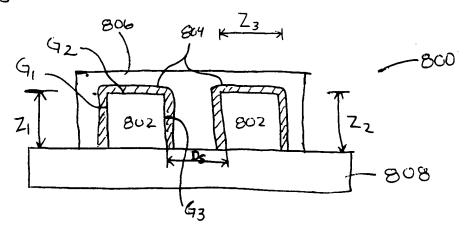
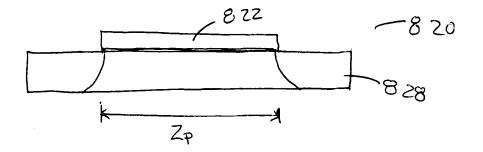


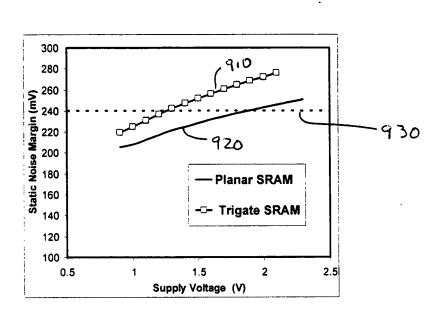
Fig. 8





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Fig.9



900

-1000 Fig. 10 film Form a semiconcluctor on a substrute. a sacrificial block on Form the semiconductor. Form an insulating layer over the sacrificial black and the semiconductor film. Form insulating spacers from the insulating layer Remove the Sacrificial block 1010 Form semiconductor fins by etching the semiconductor fin, using the insulating spacers as a Imask.

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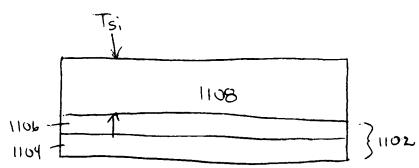


Fig. 11B

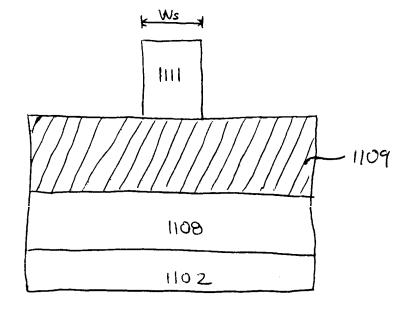


Fig. 11G

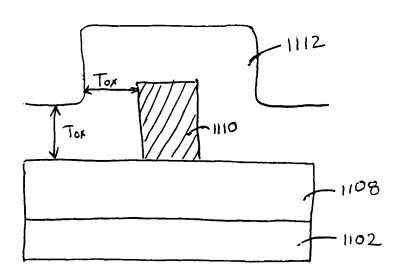


Fig.11D

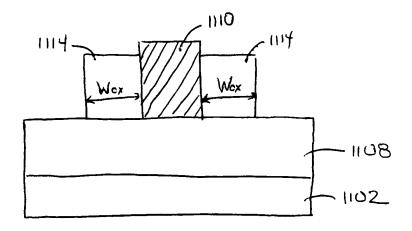


Fig. 11E

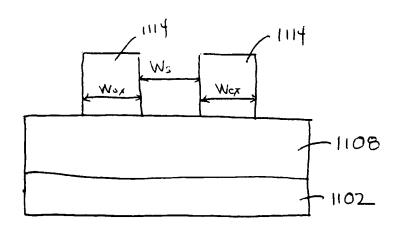


Fig. 11F

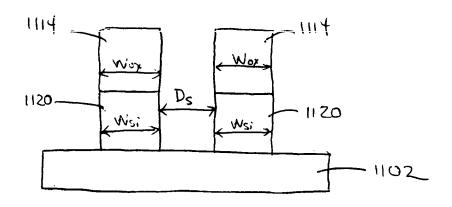


Fig. 11 G

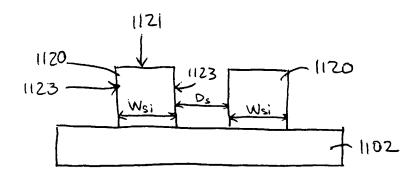


Fig. 11H

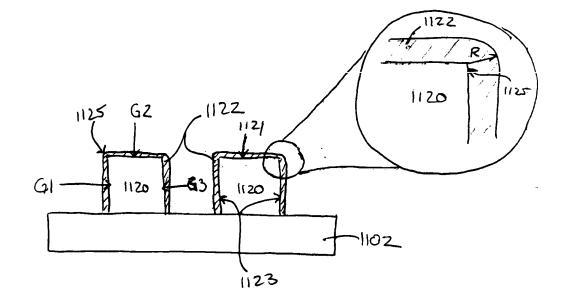


Fig. 11I..

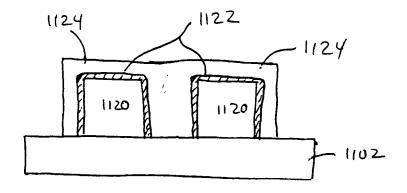


Fig. 11J

